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SHEATH STRUCTURE AROUND NEGATIVELY BIASED PROBE IN ELETRONEGATIVE PLASMA

Osaka Pref. Univ., NIFS

H. Matsuura and Y.Tomita



Background

- Langmuir probe method is widely used to determine plasma parameters. Its results is based upon the modeling of sheath potential structure.
 - new type probes (Combined force-Mach-Langmuir probe, Thermal probe) have been also proposed.
- □ Unconsistency often exists in the modeling of sheath. ○ Sometimes it has been ignored especially in fluid model.
- An instability was observed in PIC simulation of hydrogen negative sheath.
 - Is this real or only numerical phenomena?

Schematic view of fluid model



lons are accelerated by potential.

□ At sheath boundary, they reach at sound velocity.

- □ Free-fall model is usually assumed.(Zero Ti)
- Electrons are reflected by potential
- A few high energy electrons reach at wall boundary.
 Boltzmann relation is usually assumed.

Paradox of fluid model

Artificial matching technique at sheath boundary must be introduced. (But it is uncompleted.)

From the point of presheath modeling
 length of sheath is infinitely small
 spatial derivative of ion fluid velocity is infinite.

From the point of sheath modeling
 length of presheath is infinitely large
 spatial derivative of ion fluid velocity is zero.

Moreover, some assumptions (on Ti) are not always available.

- \Box Divertor plasma(Ti > Te)
- □Negative ion plasma(T+ ~ T-)

Schematic view of kinetic/PIC model



 \Box 1D in space, stationary.

□ no collision, particle source(sink)

Dependential is zero at plasma boundary and negatively biased externally at wall boundary.(not difficult to calculate floating case.)

o----- R.D.Smirnov; Dr.Thesis,

Solution of Boltzmann equation

1D steady collisionless Boltzmann equation

$$v_x \frac{\partial f_j(x, v_x)}{\partial x} + \frac{-q_j}{m_j} \frac{d\Phi}{dx} \frac{\partial f_j(x, v_x)}{\partial v_x} = 0,$$

can be transferred so that $\epsilon_{jx} = \frac{1}{2}m_j v_x^2 + q_j \Phi$ is used as independent valuable instead of v_x .

$$v_x(x,\epsilon_{jx})\frac{\partial f_j(x,\epsilon_{jx})}{\partial x} = 0,$$

So energy distribution functions of particle j is the same as those at plasma source boundary.

Boundary condition

Plasma particles(electrons, positive ions, negative ions) are supplied from boundary. In order to simulate the sheath,

- choose particle current intensity(or density) at source boundary so that Debye length is much smaller than geometry size.
- choose current(or density) ratio of positive and negative particles so that potential profile has at least one inflection point(that is perfect neutral point n+ = n-) in the geometry
 Initial velocity distribution is Maxwellian.
- □ At wall boundaries, ions and electrons are perfectly absorbed.(No reflection/No secondary electrons)

Velocity distribution function

lon

$$f(v_x) = \begin{cases} n_{is}\sqrt{\frac{m_i}{2\pi T_i}} \exp(\frac{-1}{T_i}(\frac{1}{2}m_iv_x^2 + e\Phi(x))) & (v_x < -\sqrt{\frac{2e(\Phi_s - \Phi(x))}{m_i}}) \\ 0 & (v_x > -\sqrt{\frac{2e(\Phi_s - \Phi(x))}{m_i}}) \end{cases}$$

Electron

$$f(v_x) = \begin{cases} 0 & (v_x < -\sqrt{\frac{2e(\Phi(x) - \Phi_w)}{m_e}}) \\ n_{es}\sqrt{\frac{m_e}{2\pi T_e}} \exp(\frac{-1}{T_e}(\frac{1}{2}m_e v_x^2 - e\Phi(x))) & (v_x > -\sqrt{\frac{2e(\Phi(x) - \Phi_w)}{m_e}}) \end{cases}$$

Number density

lon

$$n_i = n_{is} \exp\left(\frac{e}{T_i}(\Phi_s - \Phi)\right) \operatorname{erfc}\left(\sqrt{\frac{e}{T_i}(\Phi_s - \Phi)}\right)$$

Electron

$$n_e = n_{es} \exp\left(\frac{-e}{T_e}(\Phi_s - \Phi)\right) \left\{1 + \operatorname{erf}\left(\sqrt{\frac{e}{T_e}(\Phi - \Phi_w)}\right)\right\}$$

Inflection point of potential

From normalized Poisson equation

$$-\frac{d^2\phi}{ds^2} = \rho(s) = (n_i - n_e - n_{ni})/n_0,$$

potential profile is convex in the sheath $(\rho(s) > 0)$.

Though, $\rho(s)$ may be equal to be 0 in presheath of real plasma, we set $\rho(s)$ to be slightly positive (potential is concave) at plasma source boundary so as that inflection point of potential (and flat region around it) exists middle of the simulation geometry.

For example, if $\Phi_w/T_e = 10$ and $R_i = 1.0$, XOOPIC gives us that $-\phi = -\Phi/T_e \sim 1.7$ at the inflection point (In real presheath, $-\phi = 0.5$.), which can confirm by solving collisionless model for $\phi = e\Phi/T_e$

If $n_{is} = n_{es}, \phi \sim -1.7$.

Semi-implicit Runge-Kutta method

Kaps-Rentrop-Shapine formula

□T.Watabe et al., "Numerical software by fortran 77", (Maruzen, Tokyo, 1990)[in Japanese].

source code(main)

```
С
       parameter( neq = 2 )
                                                                                           subroutine rfunc (x, y, ydot)
       external rfunc, derf, dfunc
external fdeni, fdene
                                                                                             sheath potential eqs.
       REAL*8 ABSERR, ESTERR, RELERR
                                                                                          implicit double precision(a-h,o-z)
       DIMENSION Y(NEQ), YN(NEQ), ESTERR(NEQ)
                                                                                           parameter(neq = 2)
       DIMENSION WORK1(NEQ), WORK2(NEQ), WORK3(NEQ), WORK4(NEQ, 12)
                                                                                           dimension y(neq), ydot(neq)
       DIMENSION WORK(NEQ, NEQ), IWORK(NEQ)
                                                                                           external fdeni, fdene
С
                                                                                           common /compar/phiw, denie
       common /compar/phiw, denie
С
                                                                      rkfds option
                                                                                          phi=y(1)
       ABSERR = 1.0D-6
                                                                                           ex=y(2)
       RELERR = 0.0D+0
c
                                                           phi_w, (ni/ne)_source
                                                                                           vdot(1) = ex
       phiw=10.0d0
                                                                                    C
       denie=1 0d0
                                                                                           call fdeni(phi.deni)
c
                                                           initial value
                                                                                           call fdene(phi,dene)
       xst = 0.0d0
y(1) = 0.0d0
y(2) = 0.7d0
                                                                                    С
                                                                                           vdot(2) = denie*deni - dene
                                                                                    С
c
                                                                                           return
       xin = 0.0d0
                                                                                           end
       do 40 iout = 1,1000
                                                                                    ~
         xout=xin+0.02d0
                                                                                    0
C
                                                                                           subroutine dfunc (x, y, dfx,dfy)
          CALL KRSNAT(NEQ, RFUNC, DFUNC, XIN, XOUT, Y, INIT, RELERR, ABSERR,
                                                                                             Jacobian for sheath potential eqs.
                        YN, ESTERR, IERR, WORKO, WORK1, WORK2, WORK3, WORK4,
                        WORK, IWORK)
                                                                                           implicit double precision(a-h,o-z)
С
                                                                                           parameter(neq = 2)
         IF ((IERR .EQ. 10000) .OR. (IERR .EQ. 20000) .OR.
(IERR .EQ. 30000) .OR. (IERR .EQ. 40000)) THEN
                                                                                           dimension y(neq), dfx(neq), dfy(neq,neq)
      80
                                                                                           external dfdeni, dfdene
            WRITE(*,90) IERR
                                                                                           common /compar/phiw, denie
            stop
                                                                                    С
         end if
                                                                                           phi=v(1)
С
                                                                                           ex=y(2)
         if (yn(1).lt.(0.0d0)) then
           write(6,*) '## stop at iout = ',iout
                                                                                    (snip)
            stop
                                                                                    С
         end if
                                                                                           dfx(1) = 0.0d0
         if (yn(1).gt.(phiw*0.98d0)) then
  write(6,*) '## stop at iout = ',iout
                                                                                           dfx(2) = 0.0d0
                                                                                    с
            stop
                                                                                           call dfdeni(phi.ddeni)
         end if
                                                                                           call dfdene(phi,ddene)
c
         Y(1) = YN(1)
                                                                                           df_{V}(1,1) = 0.0d0
         Y(2) = YN(2)
                                                                                           dfy(1,2) = 1.0d0
         XIN=XOUT
                                                                                           dfy(2,1) = denie*ddeni - ddene
c
                                                                                           dfy(2,2) = 1.0d0
  40
       continue
       format(1x ,'# Error in RKFDS/KRSNAT IERR=', i7)
  90
                                                                                           return
С
                                                                                           end
       stop
                                                                                    с
```

Input parameters of source boundary

phiw=10.0d0
$$\Leftarrow \frac{-e\Phi_w}{T_e}$$

denie=1.0d0 $\Leftarrow \left(\frac{n_i}{n_e}\right)_s$
xst = 0.0d0 $\Leftarrow (x/\lambda_D)_s$
y(1) = 0.0d0 $\Leftarrow \frac{-e\Phi_s}{T_e}$
y(2) = 0.7d0 $\Leftarrow \left(-\frac{e\lambda_D}{T_e}\frac{d\Phi}{dx}\right)_s$

The effect of y(2) is mainly studied.

Sheath potential from kinetic model



Distance is normalized with Debye length.

The legends are the normalized electric field(y(2))at source boundary.

Condition for sheath establishment



Absolute value of electric field at source boundary must exceed the critical value. The long flat potential is obtain for lower electric field.

density and flow velocity



since definition of Mach number is not clear for finite Ti.

Berkeley code(XOOPIC)

2-Dimensional PIC code developed and distributed by PTSG group(Prof. C. K. Birdsall)

J.P.Verboncoueur et al.;Comp.Phys.Comm.,87(1995)199-211.
 http://ptsg.eecs.Berkeley.edu/



Simulation condition



Comparison of kinetic model and PIC



Density dependence on potential is well interpreted with the kinetic model.

Comparison of kinetic model and PIC



Sheath potential from XOOPIC



Average energy from XOOPIC



In case of right figure, though potential profile oscillates with large amplitude, no effect on ion energy is observed.

Hydrogen negative sheath

Hydrogen negative ion(H-) is important in recent NBI source plasma and detached divertor plasma with Molecular Activated Recombination(MAR).

In conventional sheath model, many assumptions, which may break in some kind of plasma, are used without checking.

So the analytical results such as famous formula $\frac{eV_f}{kT_e} = 0.5 \ln((2\pi \frac{m_e}{m_i})(1 + \frac{T_i}{T_e}))$ can not be applied to electronegative plasma only by setting $m_e \to m_i$.

In XOOPIC simulation, by changing electrons with hydrogen negative ions, the simulation becomes unstable and numbers of hydrogen positive/ negative ion in the calculation geometry oscillates with time much slower than plasma oscillation period.

Pulse function of XOOPIC

Source current intensity in XOOPIC can be controlled with six parameters (a0, a1, tdelay, trise, tpulse, tfall).



Time dependent boundary



After t=0.2e-6[s], electron injection decreases gradually and negative ion starts to be injected to keep charge neutrality.

Potential profile (n-/n+ => 1.00)



Red: t=0.31e-6[s], Blue: 1.2e-6[s Orange: 1.9e-6[s

After t=0.2e-6[s], electron injection decreases gradually and negative ion starts to be injected to keep charge neutrality.

Occurrence of instability is observed after most electrons are lost.

Velocity distribution(n-/n+=0.80)



80 percent electrons are exchanged with Hydrogen negative ions. Sheath structure is still stable. (t=1.2e-6[s])

Snap (n-/n+ => 0.50 and 0.90)



Potential profile (n-/n+ => 0.50)



In the case where 50 percent electrons are retained, no instability was observed.

Average kinetic energy(n-/n+=1.00, 0.50)



As long as there exit electrons, average kinetic energy of ions is kept constant. Collision with electrons (and also neutral gas) must have some dumping effect on instability growth.

Velocity distribution(n-/n+=0.50)



Red: H+, Green:

Positive and negative ion shows two peak distribution, but electron covers these peaks.

Two stream instability



H+ peak is inside of electron distribution.



H+ peak is separated from H- peak.

Stable

Unstable

If we can approximate velocity distribution as zero temperature beam, instability onset condition for pure negative ion plasma is

$$\frac{kV_0}{\omega_{p-}} < 2\sqrt{2}.$$

where $k \sim \frac{1}{L}$ is wave number, V_0 is peak separation of ion distribution functions, ω_{p-} is H⁻ plasma frequency.

Characteristic parameters in XOOPIC

density at sheath edge 1.5e+16[1/m^3]

electron plasma freq. 6.9e+9[1/s] Its period 0.91e-9[s] ion plasma freq. 1.6e+8[1/s] Its period 3.9e-8[s]

electron thermal velo. 1.3e+6[m/s] 4.6e-9[s] transition time ion thermal velo. 3.1e+4[m/s] transition time 1.9e-7[s] 1.9e-4[m] Debye length

Time step of PIC

2e-11[s] Instability period(?) (1-2)e-7[s] --- H+ - H-5e-9[s] --- ele. - pos.

Conclusions

- □ A kinetic sheath model was developed with Boltzmann -PoissonEquations and confirmed XOOPIC results with it.
- In order to model sheath, the choice of source boundary parametersuch as electric field and charge neutrality (ni/ne) is important.
- The length of potential plateau (presheath) in simulation is determined by boundary conditions.
- PIC simulation is applied to Hydrogen negative plasma sheath. When negative ions increase, PIC simulation shows unstable behavior. This was unexpected from analytical sheath model.

Conclusions(cont.)

- We must consider kinetic interaction between positive/ negative ions. (Two stream instability ?)
 - There exist beam components in distribution function of electronegative plasma.
- If there are some dumping channel with interaction with electrons or heavy gas molecules, fluctuation of positive ions does not develop. But pure H- plasma must be lack o such a channel.

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